

(Title: RAPT wins 2003 Advanced Technology Program award)

FOR IMMEDIATE RELEASE

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Livermore, CA – May 5, 2003 – RAPT Industries, Inc., the inventors of Reactive Atom Plasma (RAP) processing announces that it has won a coveted Advanced Technology Program award from the Department of Commerce's National Institute of Standards and Technology. The 3-year \$1.95M program will support the development and testing of a prototype system for etching and polishing optical and semiconductor materials 10 to 10,000 times faster than current methods with significantly less sub-surface damage. The project will focus on the process chemistries and control system needed to extend the capabilities of the Reactive Atom Plasma (RAP) technique, first demonstrated on a laboratory scale at Lawrence Livermore National Laboratory.

The Commerce Department's National Institute of Standards and Technology (NIST) Advanced Technology Program (ATP) supports projects that industry cannot fully fund on its own because of significant technical risks. ATP awards are made on the basis of rigorous competitive peer review considering scientific and technical merit of each proposal. In addition, awards are based on the potential for broad-based economic benefits; the need for ATP funding; and evidence of a clear commercialization pathway and broad diffusion.